IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): KERBER	Atty. Dkt.: 20-010-DIV
Serial No.: Unknown	Group Art Unit:
Filed: Concurrently herewith	Examiner:
Title: SELF-ALIGNED JUNCTION PASSIVATION FOR SUPERCONDUCTOR INTEGRATED CIRCUIT	

Commissioner for Patents
Arlington, VA 22202

Date: April 1, 2004

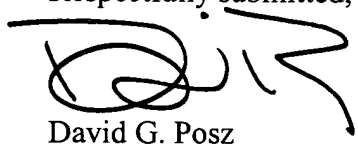
INFORMATION DISCLOSURE STATEMENT

Sir:

Pursuant to 37 C.F.R. §1.56, the reference(s) listed on the attached Form PTO-1449 is/are being submitted for consideration by the Examiner without any admission that it/they constitute(s) statutory prior art, or without any admission that it/they contain(s) subject matter that anticipates the invention or renders the invention obvious to a person of ordinary skill in the art.

The Examiner is requested to initial the attached PTO Form-1449 and to return a copy of same to the undersigned attorney as proof that the listed reference(s) has/have been considered and made of record.

Respectfully submitted,



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FORM PTO-1449	ATTY. DKT NO. 10-010-DIV	SER. NO.
	APPLICANT **KERBER**	
	FILING DATE April 1, 2004	GROUP

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	NAME	CLASS	SUB CLASS	TRANSLATION YES	TRANSLATION NO

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

		H. Kroger et al., "Selective Niobium Anodization Process for Fabricating Josephson Tunnel Junctions," Appl. Phys. Lett. 39(3), 1 August 1981, pp.280-282.
		S. Morohashi et al., "Self-aligned Contact Process for Nb/AlOx/Nb Josephson Junctions," Appl. Phys. Lett. 48(3), 20 January 1986, pp. 254-256.
		Y. Tarutani et al., "Niobium-Based Integrated Circuit Technologies," Proceedings of the IEEE, Vol. 77, No. 8, August 1989, pp. 1164-1175.
		L. Lee et al., "RHEA Process for Fine-Geometry Josephson Junction Fabrication," IEEE Transactions on Magnetics, Vol. 27, No. 2, March 1991, pp. 3133-3136.
		T. Imamura et al., "A Submicrometer Nb/AlOx/Nb Josephson Junction," J. Appl. Phys. Lett. 64(3), 1 August 1988, pp.1586-1588.
		S. Hasuo, "High-Speed Josephson Integrated Circuit Technology," IEEE Trans. Magn., v. 25, no. 2, March 1989, pp. 740 – 749.
		X. Meng et al., "Very Small Critical Current Spreads in Nb/Al-AlOx/Nb Integrated Circuits Using Low-Temperature and Low Stress ECR PECVD Silicon Oxide Films," IEEE Trans. Appl. Supercon., v. 9, no. 2, June 1999, pp. 3208 – 3211.
		A. Bhat et al., "A 10 GHz Digital Amplifier in an Ultra-Small-Spread High-Jc Nb/AlOx/Nb Integrated Circuit Process," IEEE Trans. Appl. Supercon., v. 9, no. 2, June 1999, pp. 3232 – 3236.

EXAMINER	DATE CONSIDERED

Rev. 10/94 (Form 3.05)